

<b>Notice of References Cited</b>	Application/Control No. 10/665,998	Applicant(s)/Patent Under Reexamination SCHAADT ET AL.	
	Examiner Eric B. Chen	Art Unit 1765	Page 1 of 1

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	X	Ashurst et al., Journal of Microelectromechanical Systems, March 2001, Vol. 10, No. 1, pp. 41-49.

\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.